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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/711,649	09/29/2004	Kohei Kawamura	SSIT-114	5648
37694 7	590 03/07/2006		EXAM	INER
•	RON & EVANS, LLP	HARRISON, MONICA D		
2700 CAREW TOWER 441 VINE STREET			ART UNIT	PAPER NUMBER
CINCINNATI,	CINCINNATI, OH 45202			

DATE MAILED: 03/07/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	10/711,649	KAWAMURA ET AL.				
Office Action Summary	Examiner	Art Unit				
	Monica D. Harrison	2813				
The MAILING DATE of this communication ap Period for Reply	opears on the cover sheet with the	correspondence address				
A SHORTENED STATUTORY PERIOD FOR REP WHICHEVER IS LONGER, FROM THE MAILING I - Extensions of time may be available under the provisions of 37 CFR 1 after SIX (6) MONTHS from the mailing date of this communication. If NO period for reply is specified above, the maximum statutory period Failure to reply within the set or extended period for reply will, by statu Any reply received by the Office later than three months after the mail earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNICATIO .136(a). In no event, however, may a reply be tild d will apply and will expire SIX (6) MONTHS from tte, cause the application to become ABANDONE	N. mely filed n the mailing date of this communication. ED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 29	September 2004.					
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closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims						
4)⊠ Claim(s) <u>1-26</u> is/are pending in the application.						
4a) Of the above claim(s) is/are withdrawn from consideration.						
5) Claim(s) is/are allowed.						
6)⊠ Claim(s) <u>1-26</u> is/are rejected.	i)⊠ Claim(s) <u>1-26</u> is/are rejected.					
·						
8) Claim(s) are subject to restriction and	or election requirement.					
Application Papers						
9)☐ The specification is objected to by the Examiner.						
10) ☐ The drawing(s) filed on is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).						
11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.						
Priority under 35 U.S.C. § 119						
 12) ☐ Acknowledgment is made of a claim for foreignal All b) ☐ Some * c) ☐ None of: 1.☐ Certified copies of the priority docume 2.☐ Certified copies of the priority docume 	nts have been received.					
 3. Copies of the certified copies of the prapplication from the International Bure * See the attached detailed Office action for a limited of the certified copies of the praper application from the certified copies of th	eau (PCT Rule 17.2(a)).					
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/O Paper No(s)/Mail Date 1/2/06 1/2/05 4/14	4) ☐ Interview Summar Paper No(s)/Mail I 5) ☐ Notice of Informal	ry (PTO-413)				

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DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only, if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 1-5, 7 and 12 are rejected under 35 U.S.C. 102(e) as being anticipated by Sieber et al (US 2005/0176230 A1).

- 1. Regarding claim 1, Sieber et al discloses a method of processing a dielectric film, the method comprising: providing a substrate having a fluorocarbon dielectric film deposited thereon (Figure 2, reference 26), the film having an exposed surface containing contaminant (pp. 5-6, paragraphs 0051-0054); and treating the exposed surface with a supercritical carbon dioxide fluid to clean the exposed surface of the contaminants and provide surface termination (pg. 4, paragraph 0045).
- 2. Regarding claim 2, Sieber et al discloses wherein the contaminants comprise CH_x, H₂O, OH, or HF, or a combination of two or more thereof (pp. 5-6, paragraph 0053).
- Regarding claim 3, Sieber et al discloses wherein the supercritical carbon dioxide fluid further comprises a solvent (pg. 4, paragraph 0045).
- 4. Regarding claim 4, Sieber et al discloses wherein the solvent comprises an alcohol or a silicon-containing chemical, or a combination thereof (pg. 4, paragraph 0045).

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5. Regarding claim 5, Sieber et al discloses wherein the alcohol comprises methanol, ethanol, propanol, or butanol, or a combination of two or more thereof (pp. 4-5, paragraph 0046).

- 6. Regarding claim 7, Sieber et al discloses wherein the surface termination comprises C-F functional groups or Si-Me₃ functional groups (pp. 5-6, paragraph 0053).
- 7. Regarding claim 12, Sieber et al discloses depositing a metal-containing film onto the treated surface of the fluorocarbon film, wherein the surface termination improves adhesion of the metal-containing film to the fluorocarbon film (Figure 3, references 32 and 34).

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 6, 8-11 and 13 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sieber et al (US 2005/0176230 A1) in view of Bhanap et al (US 2005/0095840 A1).

8. Sieber et al discloses all above subject matter except a silicon containing chemical (claims 6, 8 and 10) and a nitrated fluorocarbon film (claim 11).

Bhanap et al discloses a silicon containing chemical (pg.3, paragraph 0027)) and a nitrated fluorocarbon film (pp. 4-5, paragraph 0036).

It is obvious, at the time the invention was made, for one having ordinary skill in the art, to modify Sieber et al with the teachings of Bhanap et al, for the purpose of using silicon containing chemicals in a solvent because they produce a low dielectric constant and the nitrated hydrocarbons are designed to be dissolved in any suitable solvent.

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9. Regarding claim 9, Sieber et al discloses wherein the alcohol comprises methanol, ethanol, propanol, or butanol, or a combination thereof (pp. 4-5, paragraph 0046).

- Regarding claim 12, Sieber et al discloses depositing a metal-containing film onto the treated surface of the fluorocarbon film, wherein the surface termination improves adhesion of the metal-containing film to the fluorocarbon film (Figure 3, references 32 and 34).
- 11. Regarding claim 13, Sieber et al discloses wherein the metal-containing film comprises tantalum (pg.3, paragraph 0035).

Claims 14-26 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sieber et al (US 2005/0176230 A1) in view of Bhanap et al (US 2005/0095840 A1).

patterned fluorocarbon dielectric film formed thereon (Figure 2, reference 26) and the patterned fluorocarbon dielectric film having an exposed surface containing contaminants (pp. 5-6, paragraphs 0051-0054); treating the exposed surface with a supercritical carbon dioxide fluid to clean the exposed surface of the contaminants and provide surface termination (pg. 4, paragraph 0045). However, Sieber et al does not disclose the patterned fluorocarbon dielectric film having one or more vias or trenches or a combination thereof.

Bhanap et al discloses the patterned fluorocarbon dielectric film having one or more vias or trenches or a combination thereof (pg. 2, paragraph 0020).

It is obvious, at the time the invention was made, for one having ordinary skill in the art, to modify Sieber et al with the teachings of Bhanap et al, for the purpose of forming trenches and vias in an dielectric film in order to subject the dielectric film to a treatment which removes at least a portion of carbon containing moieties and reduces hydrophobicity of the dielectric film.

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Regarding claim 15, Sieber et al discloses wherein the contaminants comprise CH_x, H₂O, OH, or HF, or a combination of two or more thereof (pp. 5-6, paragraph 0053).

- 14. Regarding claim 16, Sieber et al discloses wherein the supercritical carbon dioxide fluid further comprises a solvent (pg. 4, paragraph 0045).
- 15. Regarding claim 17, Sieber et al discloses wherein the solvent comprises an alcohol or a silicon-containing chemical, or a combination thereof (pg. 4, paragraph 0045).
- 16. Regarding claim 18 and 22, Sieber et al discloses wherein the alcohol comprises methanol, ethanol, propanol, or butanol, or a combination of two or more thereof (pp. 4-5, paragraph 0046).
- 17. Regarding claims 19, 21 and 23, Bhanap et al wherein the silicon-containing chemical comprises hexamethyldisilane, hexamethyldisilazane, dimethylsilyldlethylamine, tetramethyldisilazane, trimethylsilyldimethylamine, dimethylsilyldimethylamine, trimethylsilyldiethylamine, bis-trimethylsilyl-urea, bistdimethylaminolmethyl silane, bis(dimethylamino)methyl silane, dimethylaminopenomethyldisilane, dimethylaminodimethyldlsilane, or a combination of two or more thereof (pg.3, paragraph 0027).
- 18. Regarding claim 20, Sieber et al discloses wherein the surface termination comprises C-F functional groups or Si-Me₃ functional groups (pp. 5-6, paragraph 0053).
- 19. Regarding claim 24, Bhanap et al discloses wherein the fluorocarbon film comprises a nitrated fluorocarbon (pp. 4-5, paragraph 0036).
- 20. Regarding claim 25, Sieber et al discloses depositing a metal-containing film onto the treated surface of the fluorocarbon film, wherein the surface termination improves adhesion of the metal-containing film to the fluorocarbon film (Figure 3, references 32 and 34).

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21. Regarding claim 26, Sieber et al discloses wherein the metal-containing film comprises tantalum (pg.3, paragraph 0035).

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Monica D. Harrison whose telephone number is 571-272-1959.

The examiner can normally be reached on M-F 7:00am-3:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead Jr. can be reached on 571-272-1702. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Monica D. Harrison AU 2813

mdh

March 3, 2006

CARL WHITEHEAD, JR

SUPERVISORY PATENT EXAMINER TECHNOLOGY CENTER 2800